PROCEEDINGS OF SPIE

Advanced Fabrication Technologies for Micro/Nano Optics and Photonics IV

Winston V. Schoenfeld
Jian Jim Wang
Marko Loncar
Thomas J. Suleski
Editors

25–26 January 2011
San Francisco, California, United States

Sponsored and Published by
SPIE

Volume 7927

Proceedings of SPIE, 0277-786X, v. 7927

SPIE is an international society advancing an interdisciplinary approach to the science and application of light.

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Please use the following format to cite material from this book:
Author(s), "Title of Paper," in *Advanced Fabrication Technologies for Micro/Nano Optics and Photonics IV*, edited by Winston V. Schoenfeld, Jian Jim Wang, Marko Loncar, Thomas J. Suleski, Proceedings of SPIE Vol. 7927 (SPIE, Bellingham, WA, 2011) Article CID Number.

ISSN 0277-786X
ISBN 9780819484642

Published by
SPIE
P.O. Box 10, Bellingham, Washington 98227-0010 USA
Telephone +1 360 676 3290 (Pacific Time) · Fax +1 360 647 1445
SPIE.org

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Printed in the United States of America.

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